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ISIF 2019 // UCD CAMPUS // DUBLIN
11-14 AUGUST 2019

Influences on the nonlinearity of HfO_2 based ferroelectric synapses (FeFETs) for neuromorphic computing

13.08.2019

M. Lederer, T. Kämpfe, T. Ali, Y. Gao, K. Seidel



Fraunhofer
IPMS



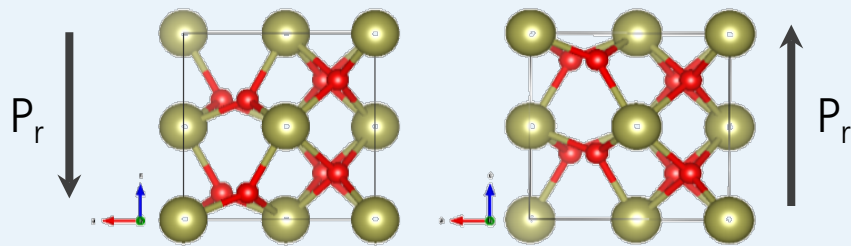
ISIF2019.COM



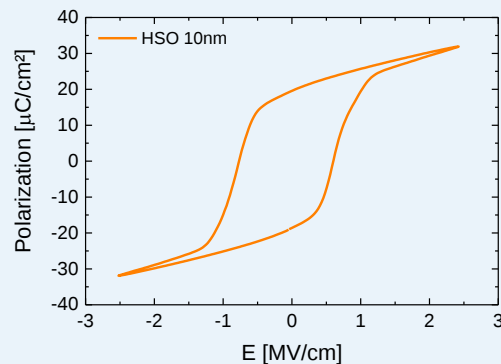
Ferroelectric Fieldeffect Transistor (FeFET)

Ferroelectricity in HfO_2

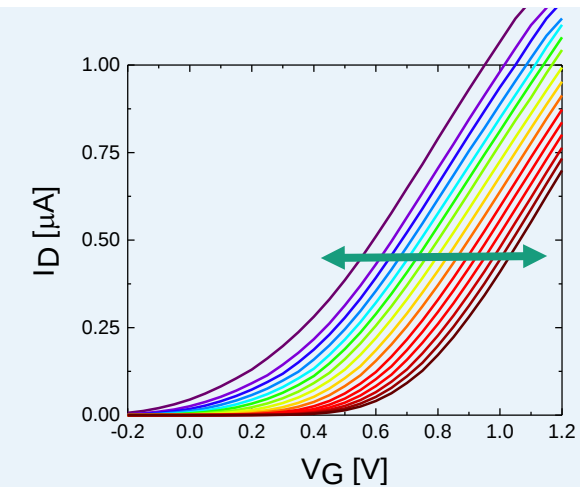
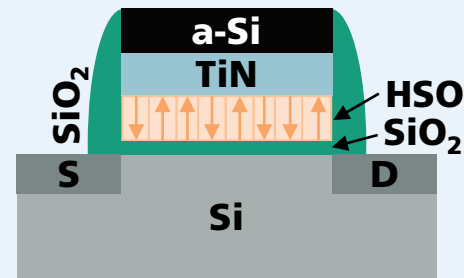
Orthorhombic (Pca2_1)



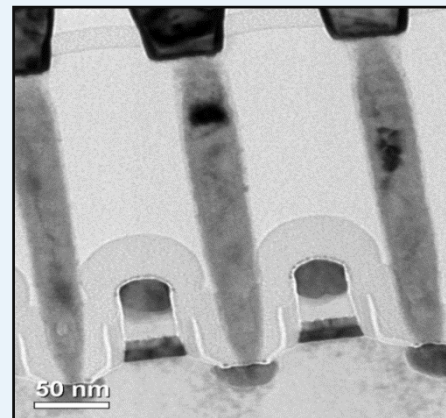
- Stabilized by Dopants, Stress, ...



FeFET Gate Stack



28nm Proof of Concept



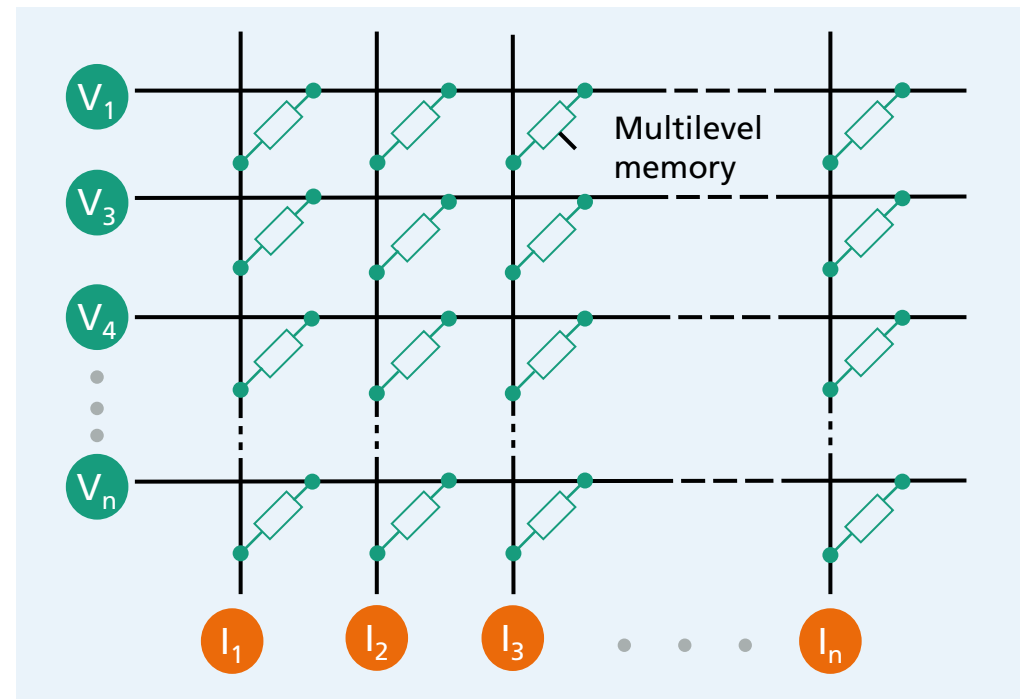
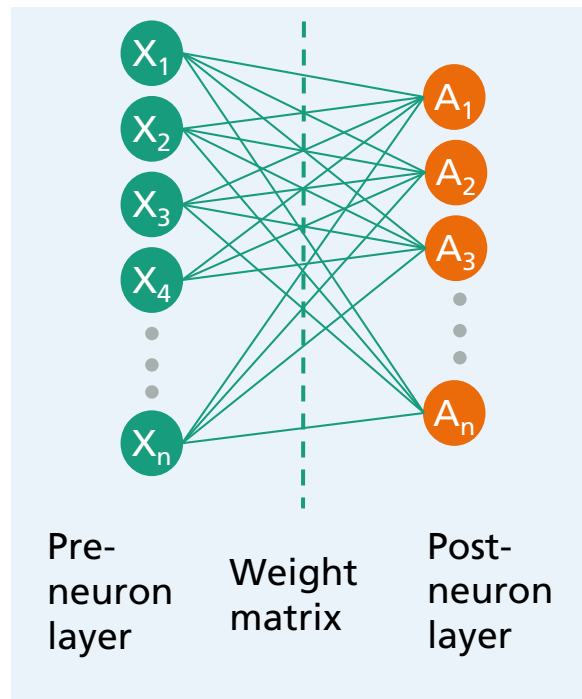
- Gate-First
- $\Delta V_T = 1\text{-}1.2 \text{ V}$
- $\pm 5\text{V}, < 100 \text{ ns}$
- 10^4 endurance
- 10y retention

J. Müller et al., VLSI (2012)

Neuromorphic Computing

Dot-product engine

- Conductance of crossbar array represent weight matrix
- Level-based representation
- Most efficient for fully connected layers



Non-Linearity Coefficient

1. Nonlinearity Fit:

$$I_{p,d} = B \left(1 - \exp \left(\frac{P - D}{A} \right) \right) + C$$

P := Pulse Number

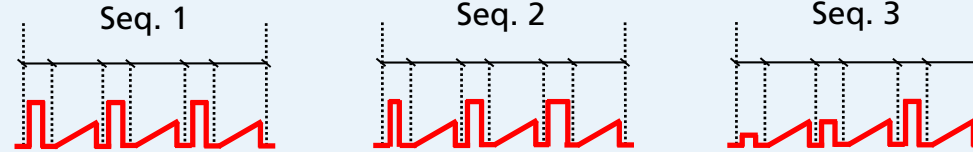
D := Start Pulse Number

2. Nonlinearity Coefficient:

$$\alpha_{p,d} = \frac{1.726}{A + 0.162}$$

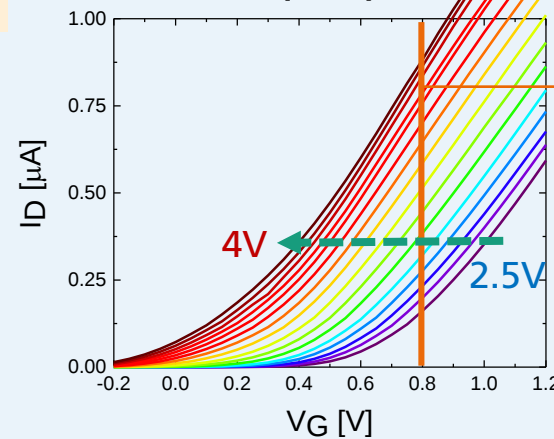
M. Jerry et al., IEDM (2017)

Signal Shape

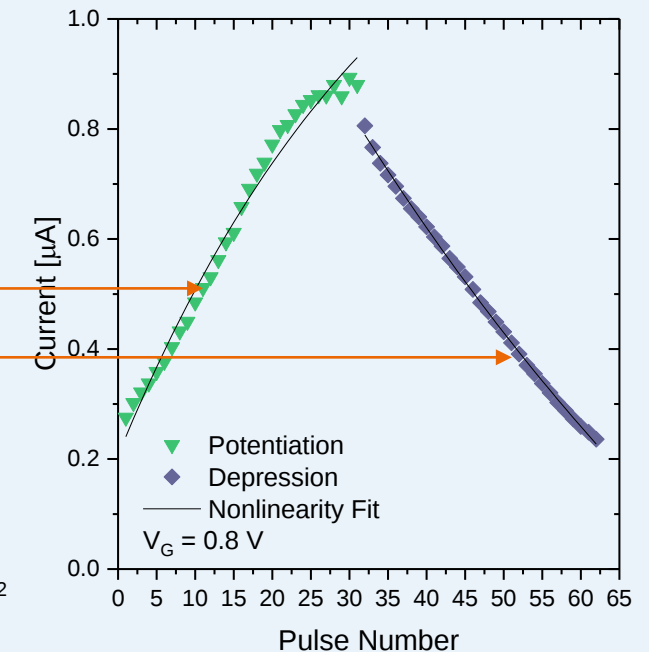
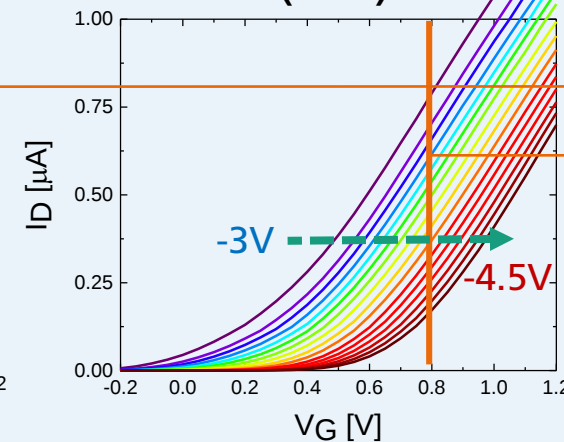


Seq. 3: 150ns
W: 50 μm , L: 25 μm

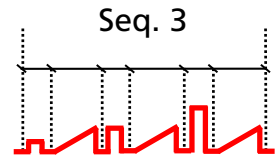
Potentiation (LTP):



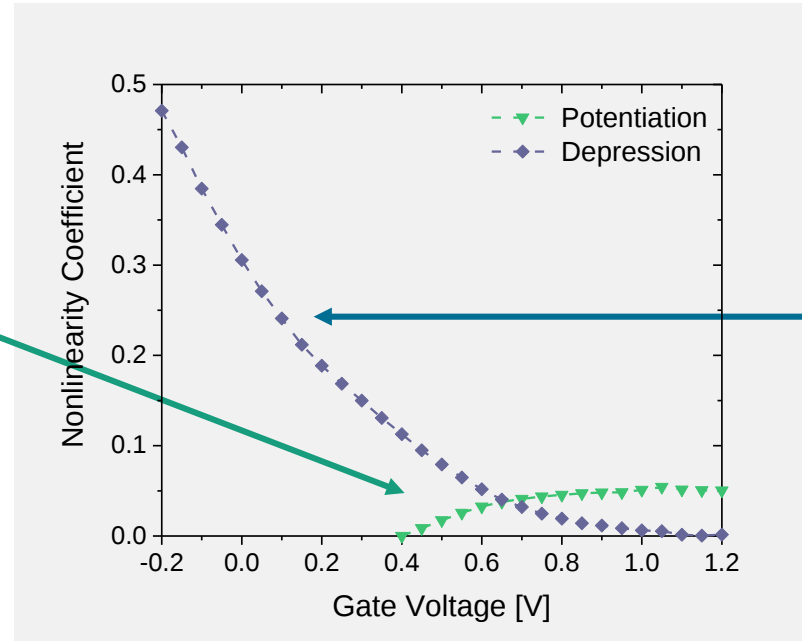
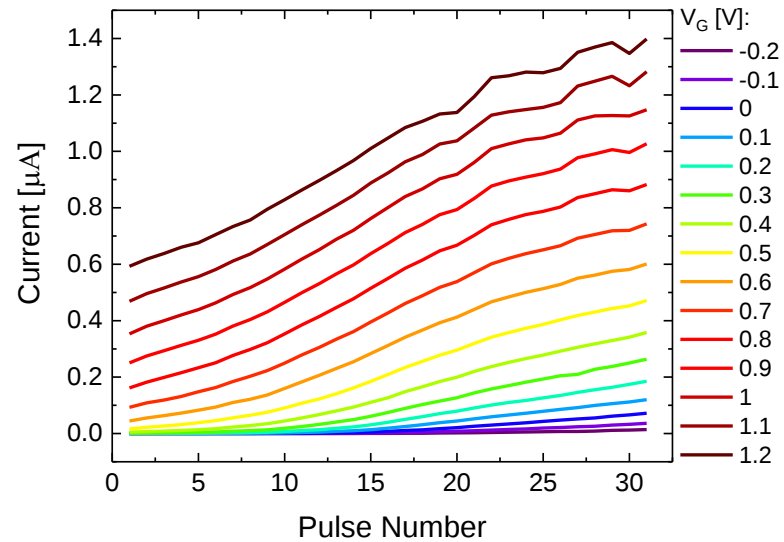
Depression (LTD):



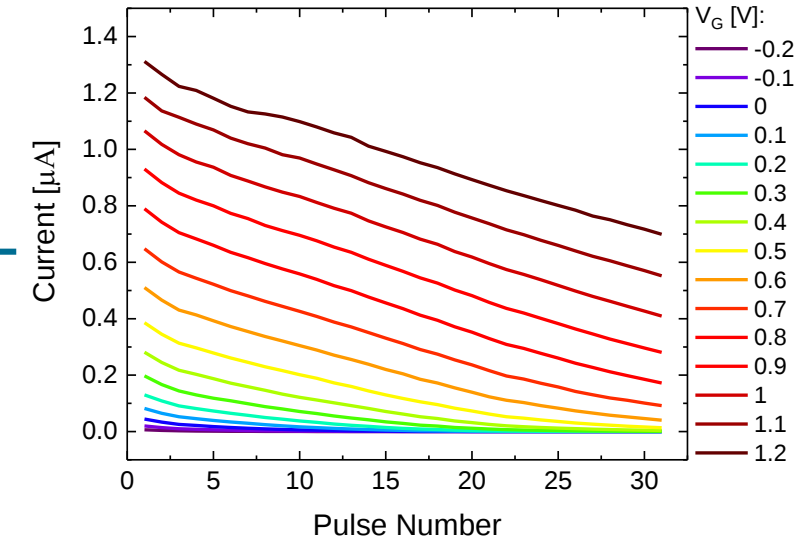
Influence of the Gate Voltage



Potentiation:

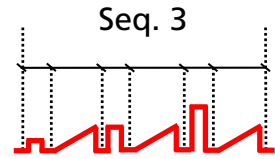


Depression:

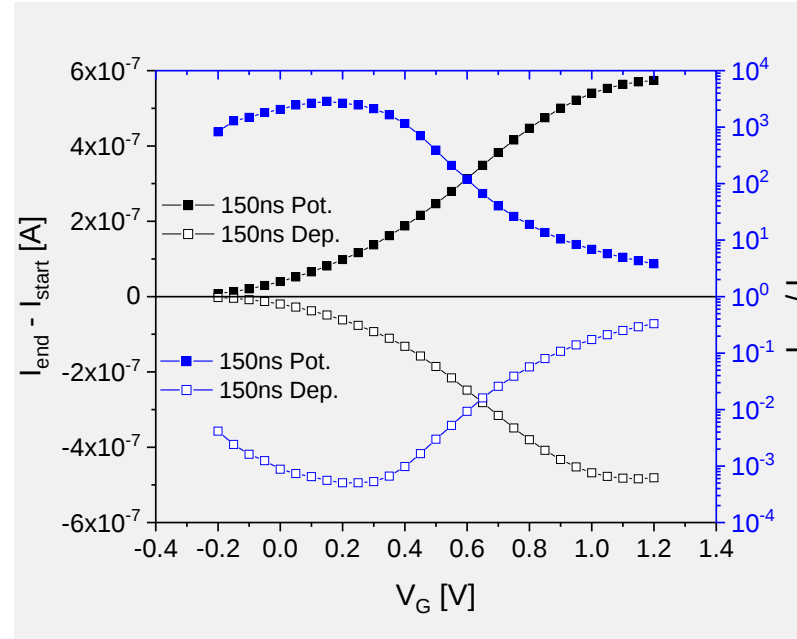
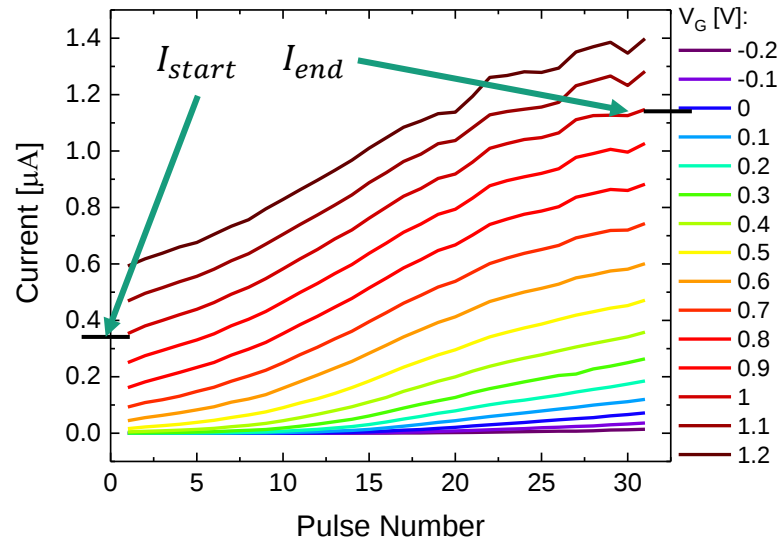


- Nonlinearity is strongly dependent on gate voltage

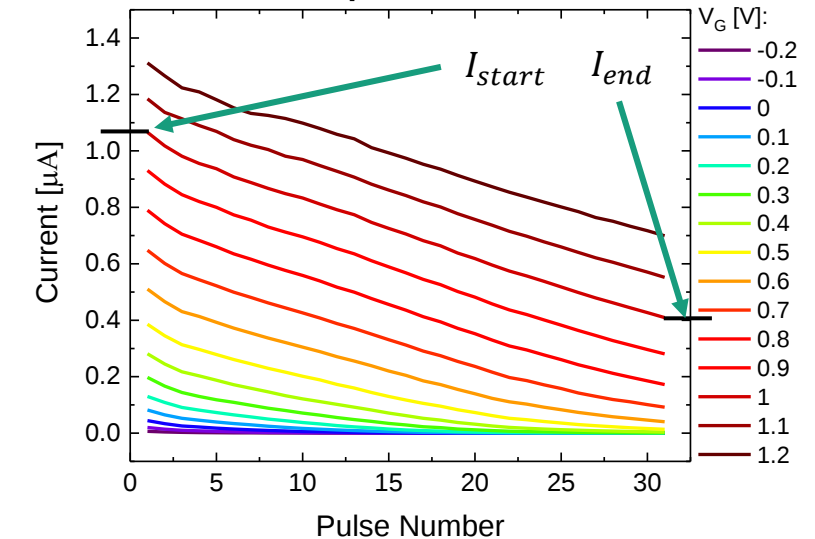
Influence of the Gate Voltage



Potentiation:



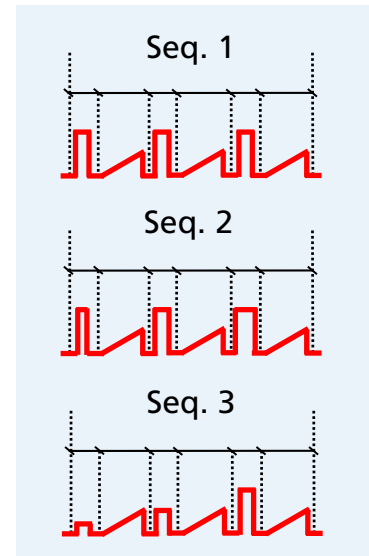
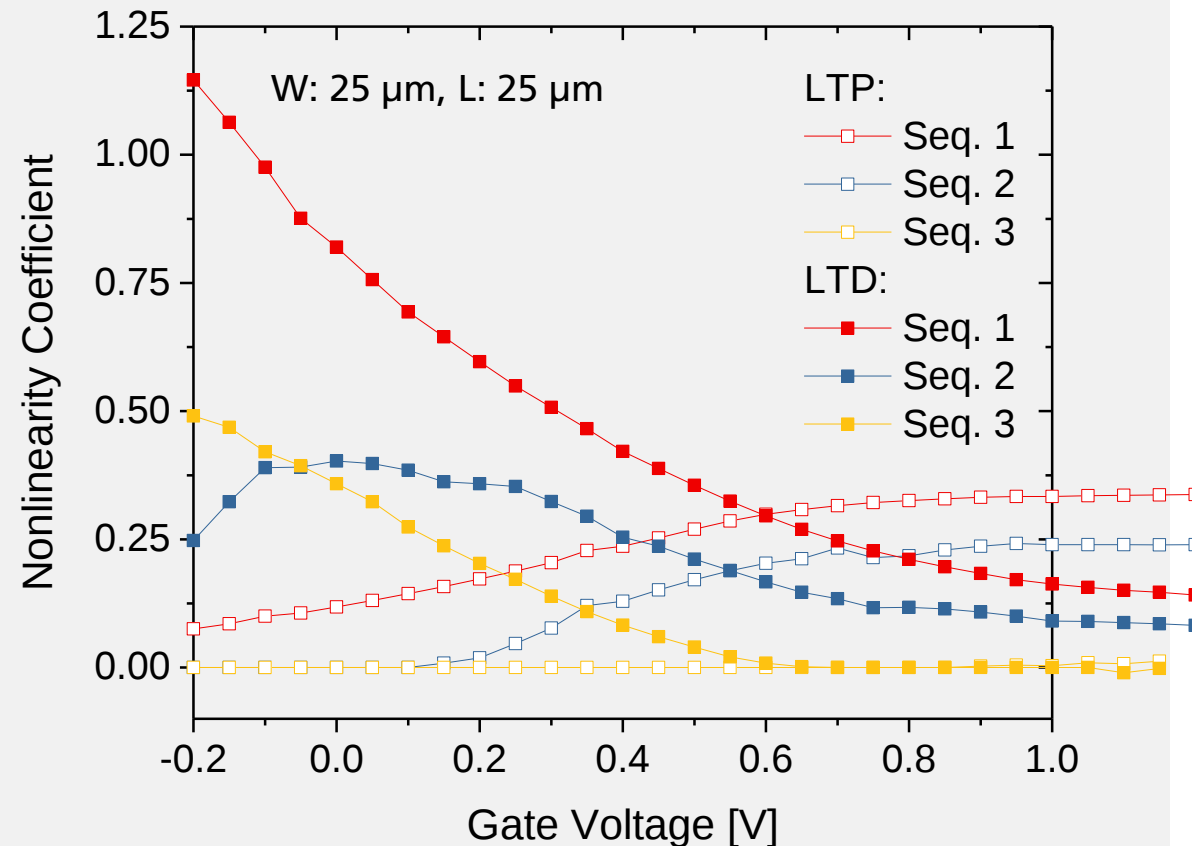
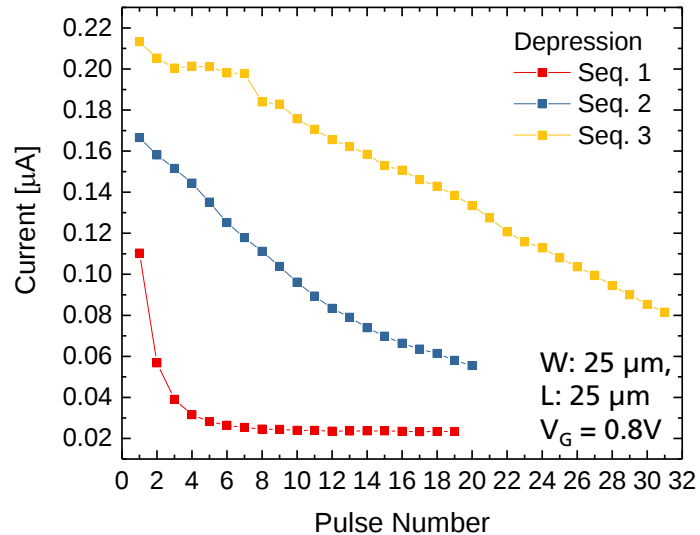
Depression:



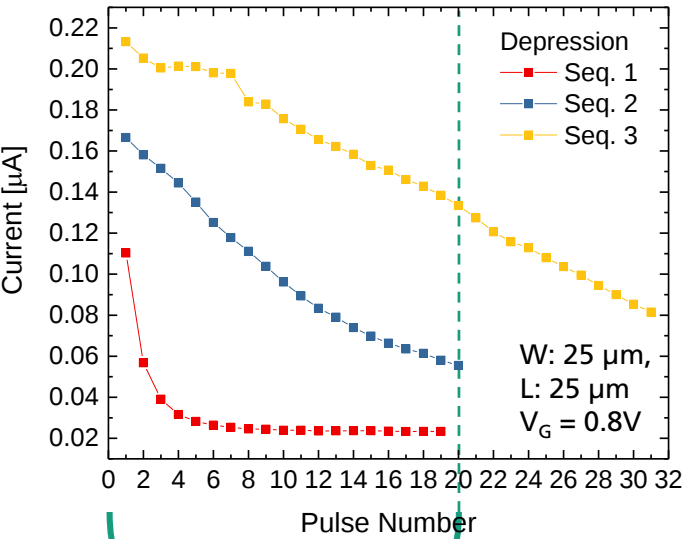
- Variance strongly dependent on gate voltage
- Relative and absolute variance show maximum at different gate voltages

Sequence 1 – 3: Nonlinearity

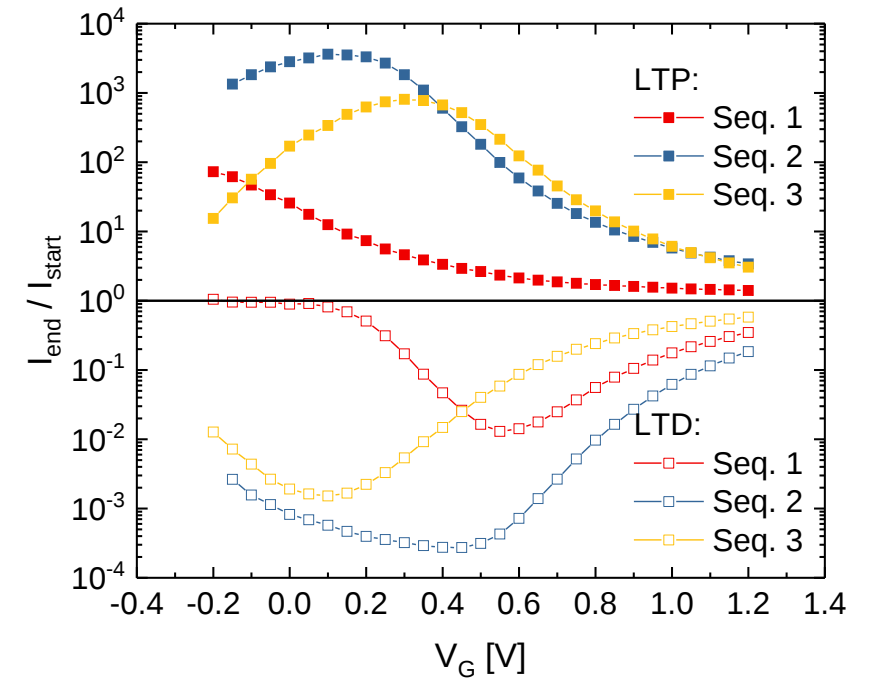
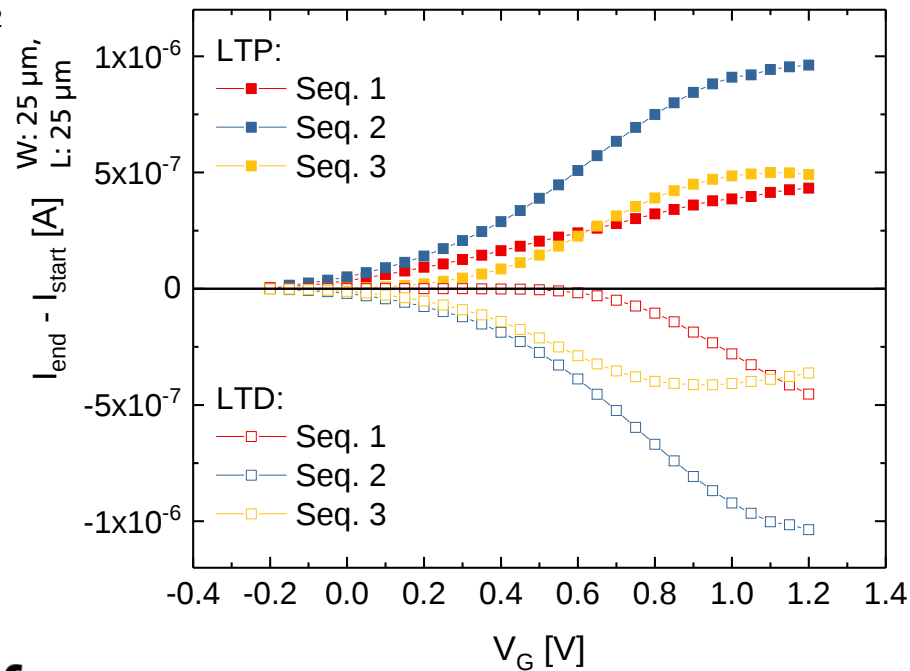
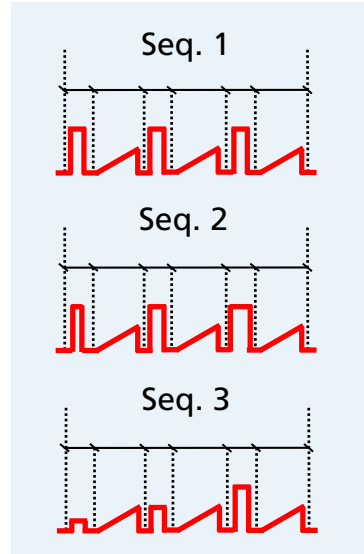
- Sequence 3 shows lowest nonlinearity



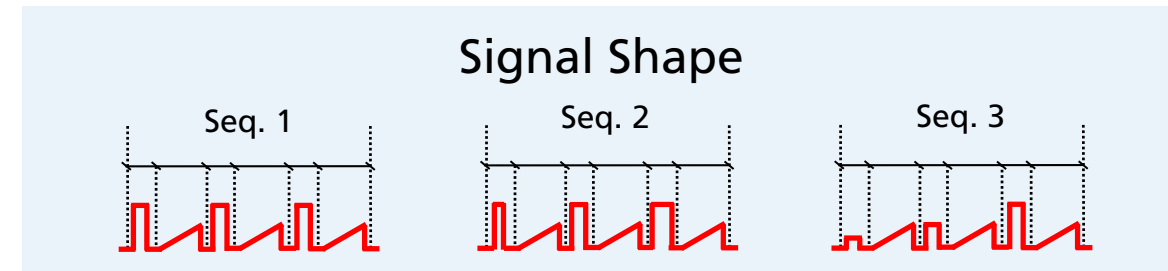
Sequence 1 – 3: Variance (I_{on}/I_{off})



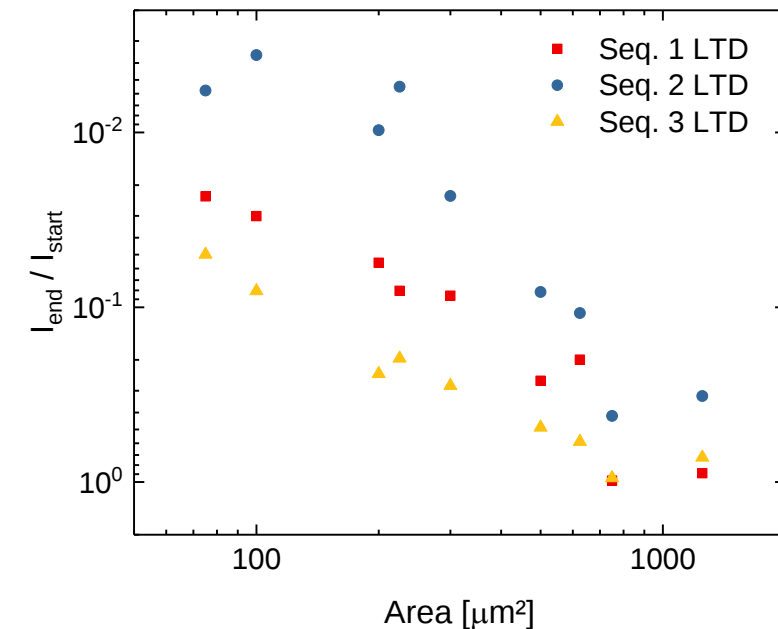
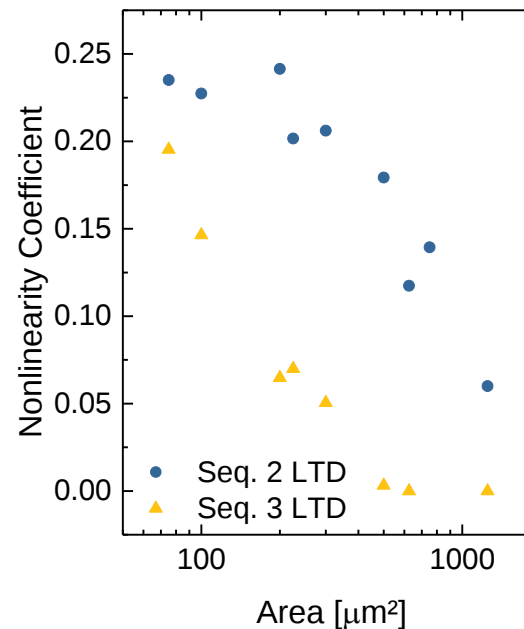
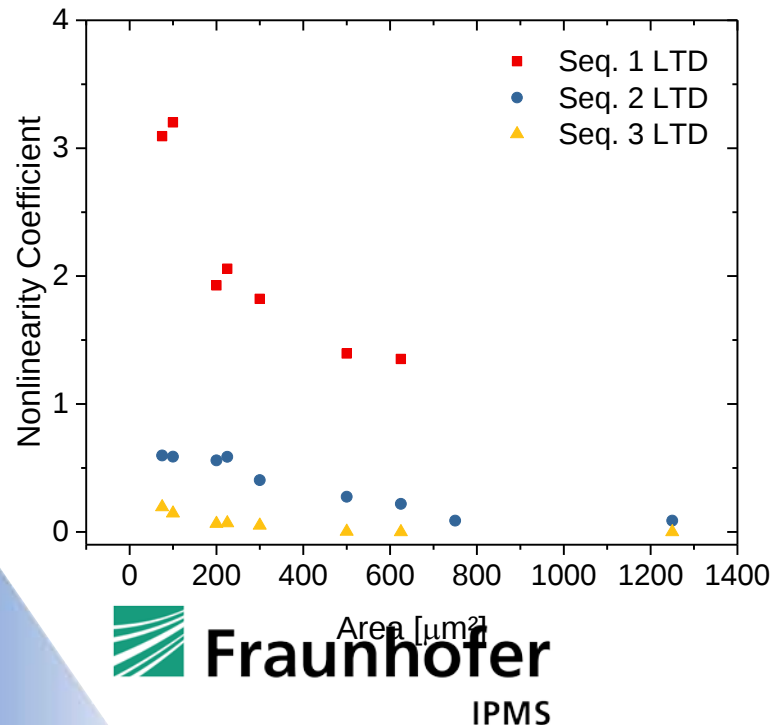
- Seq. 2 & 3 less asymmetric
- Higher variance for Seq. 2 & 3
- Variance can be improved by using more pulses (Seq. 3)



Sequence 1 – 3: Area Scaling

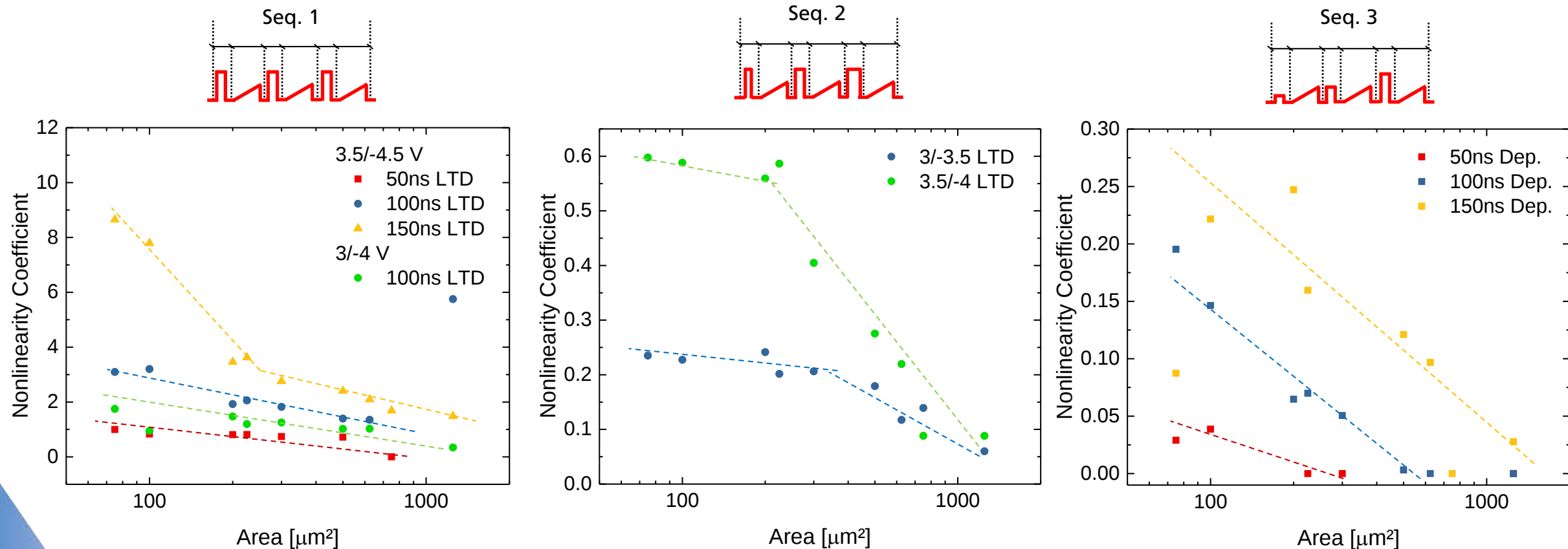


- Seq. 1 shows a very rapid increase in nonlinearity with area scaling
- Seq. 2 and 3 show slower increase, could be used for smaller devices
- Origin lies in domain structure and nucleation limited switching

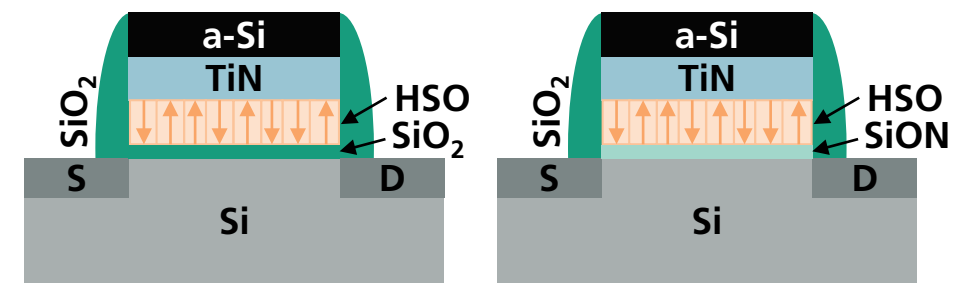
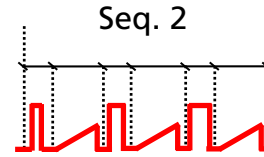


Sequence 1 – 3: Possible Adjustments for Area Scaling

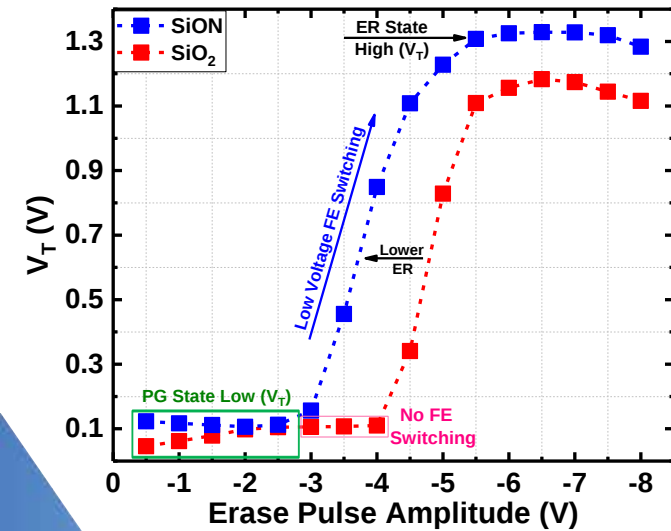
- Adjusting signal shape for smaller devices improves nonlinearity



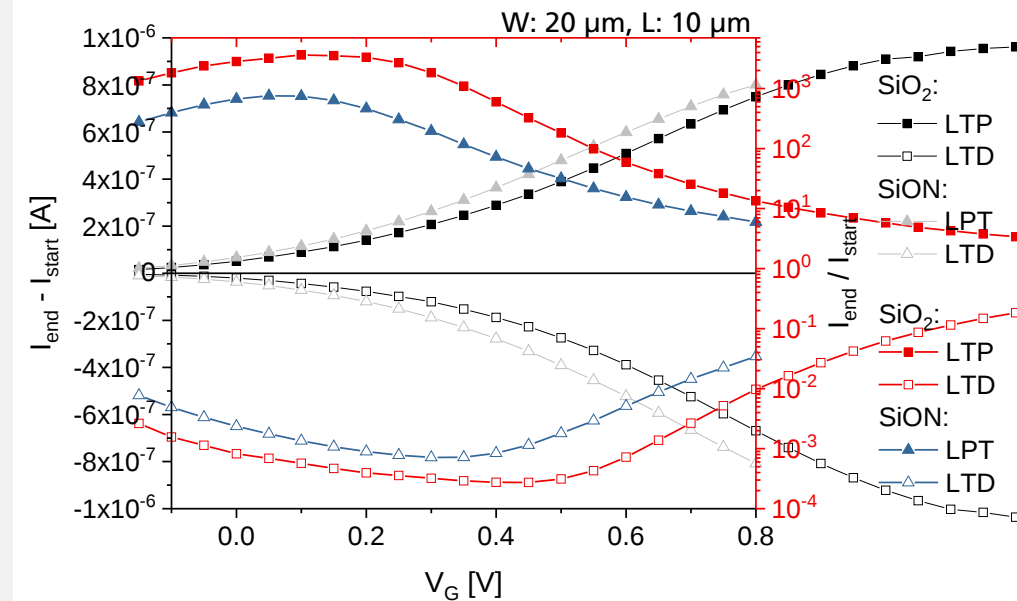
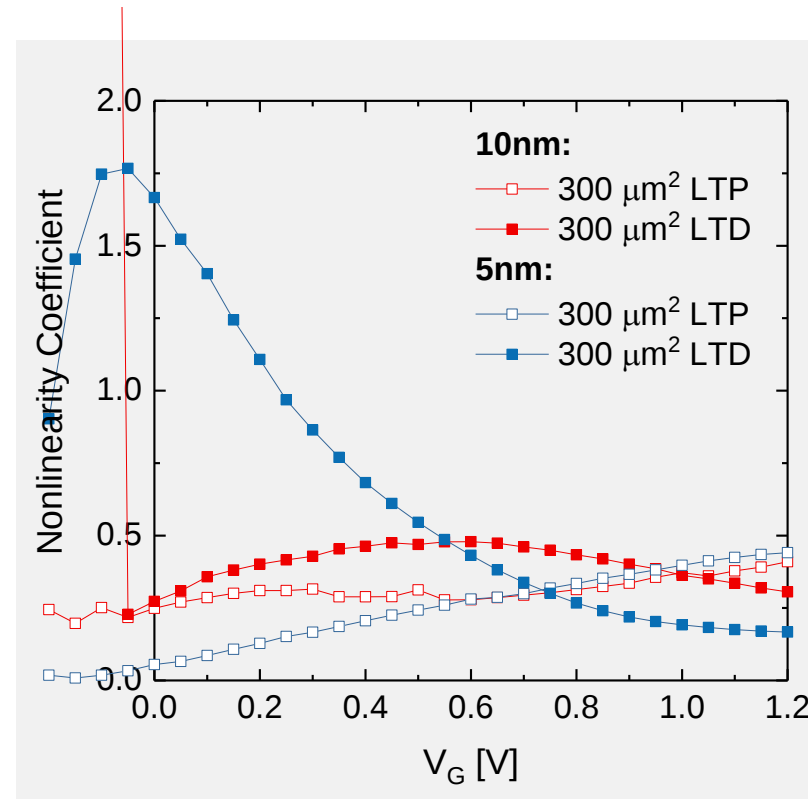
FeFET SiO₂ vs SiON



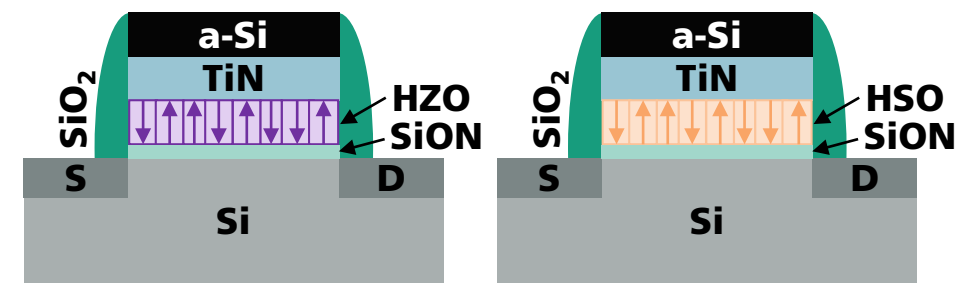
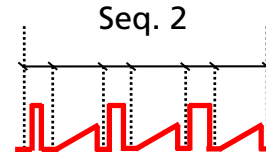
- SiON: Lower voltages necessary to switch fully → Increase in nonlinearity



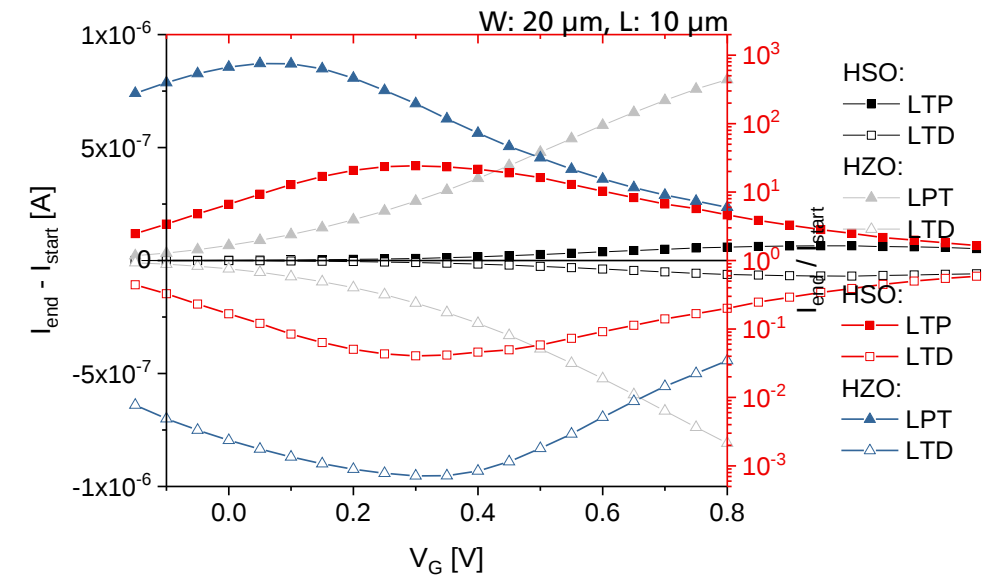
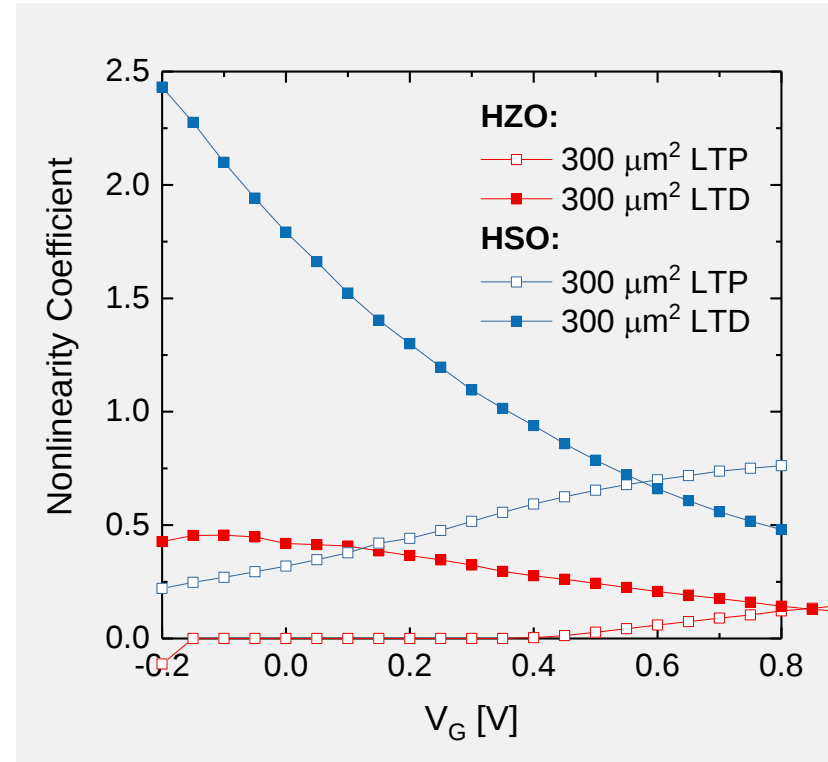
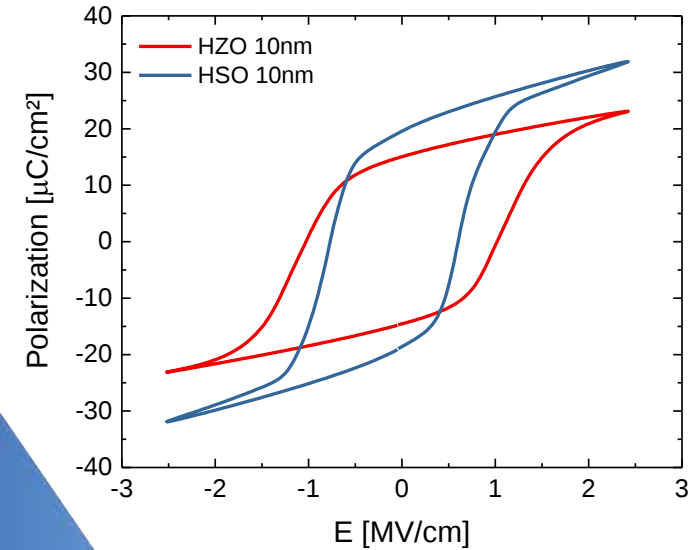
T. Ali et al., TED (2018)



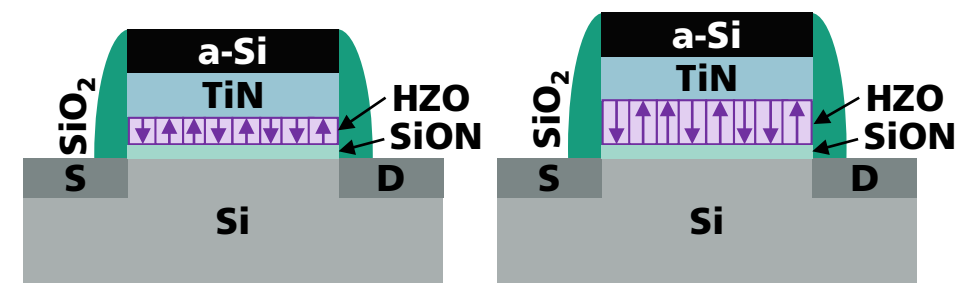
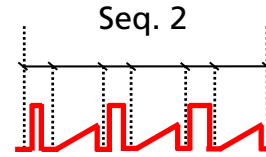
FeFET HSO vs HZO



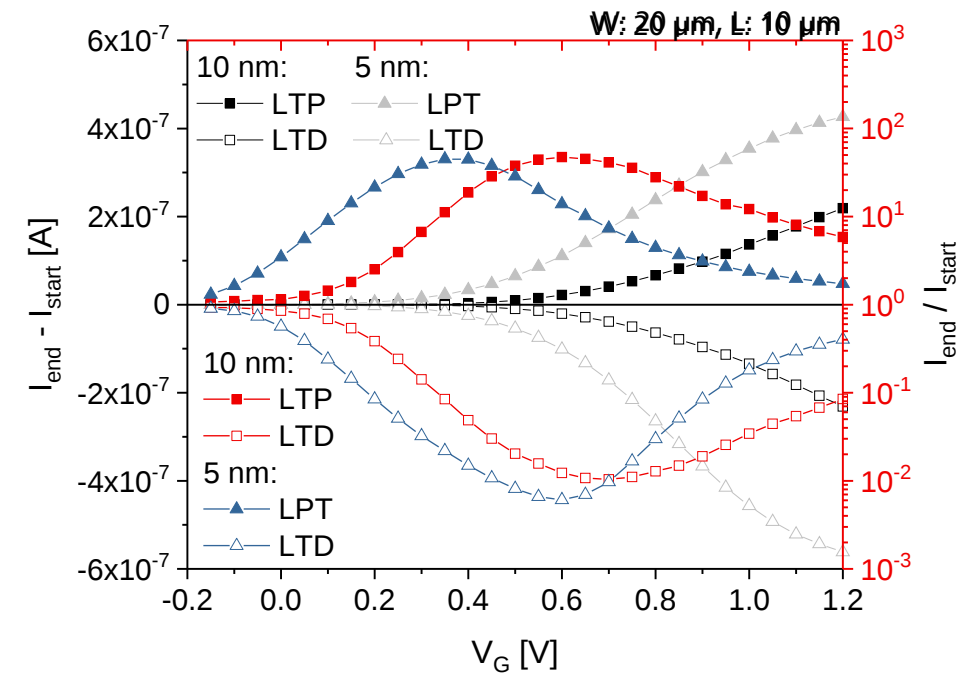
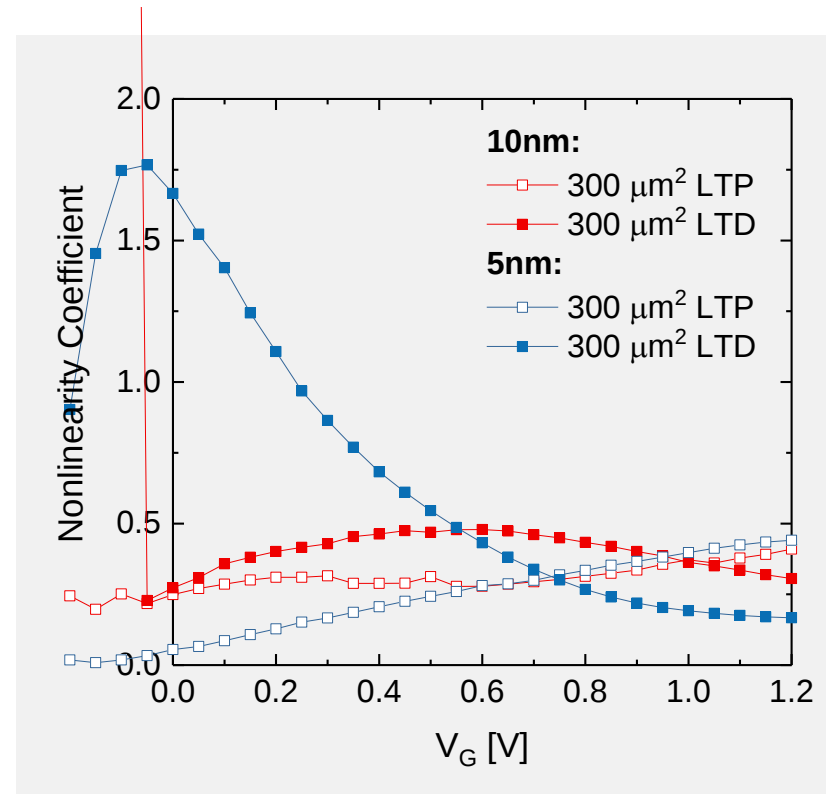
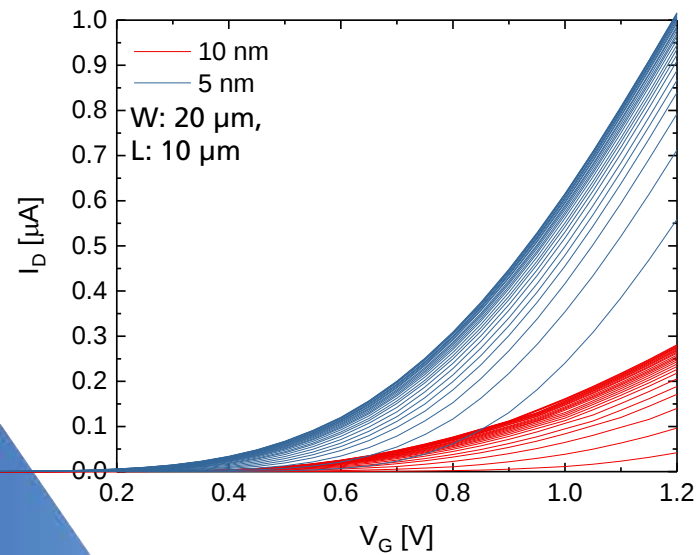
- Lower Variance due to larger MW (FeFET Comparison) not reaching saturation current
- More Subloop Behaviour → Lower nonlinearity coefficient



FeFET thickness influence

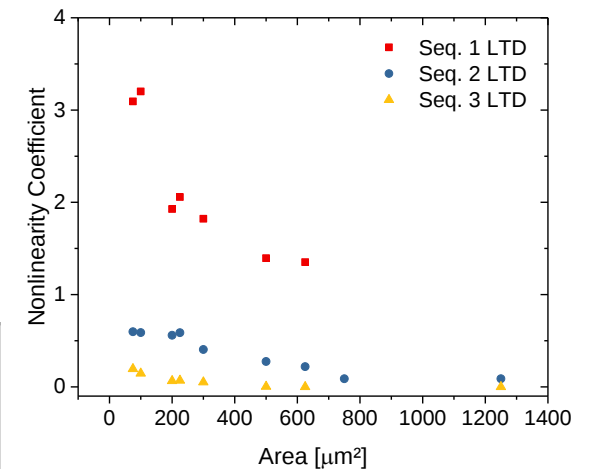
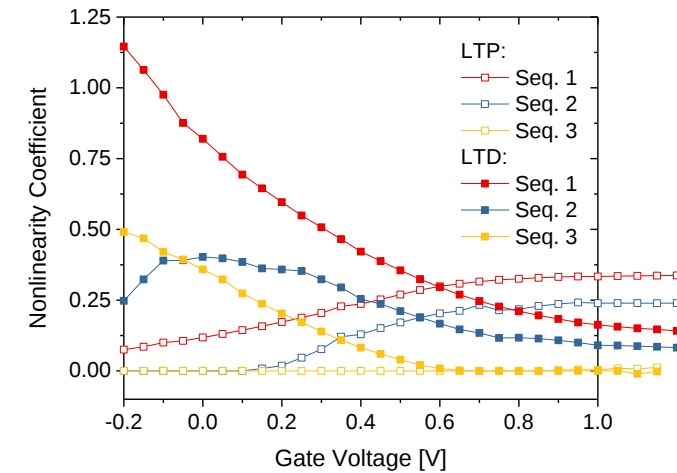
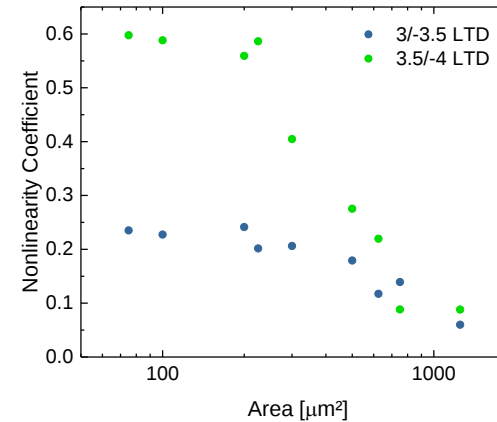
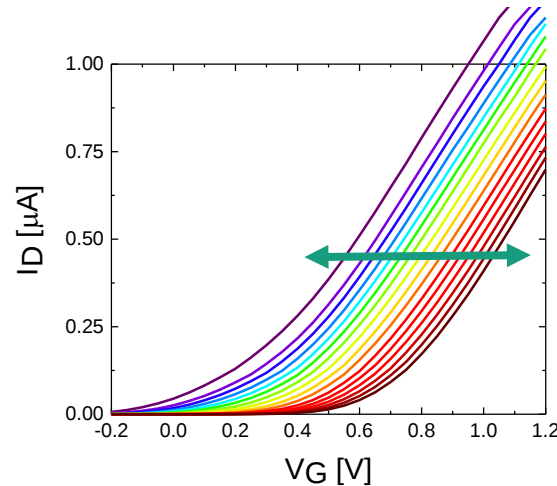
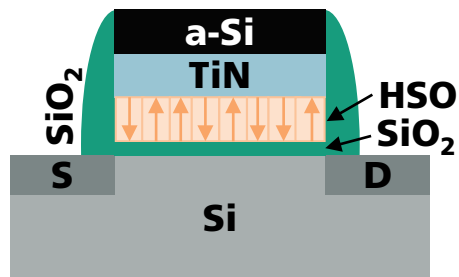


- Thinner film results in an increased electrical field → Compressed / steeper behaviour with V_G

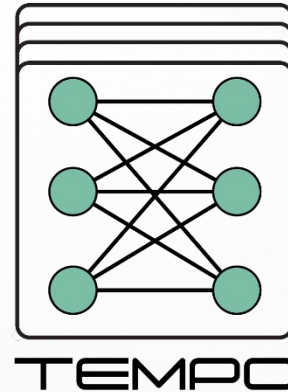


Conclusion & Outlook

- Nonlinearity and variance can be tuned by signal shape and gate voltage
- Trade-off between variance and nonlinearity
- Scaling of area without strong increase in nonlinearity possible for sequence 2 and 3



Acknowledgements



We received funding within the ECSEL Joint Undertaking project TEMPO in collaboration with the European Union's H2020 Framework Program (H2020/2014-2020) and National Authorities, under grant agreement number 783176.



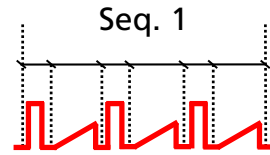
Bundesministerium
für Bildung
und Forschung



Freistaat
SACHSEN

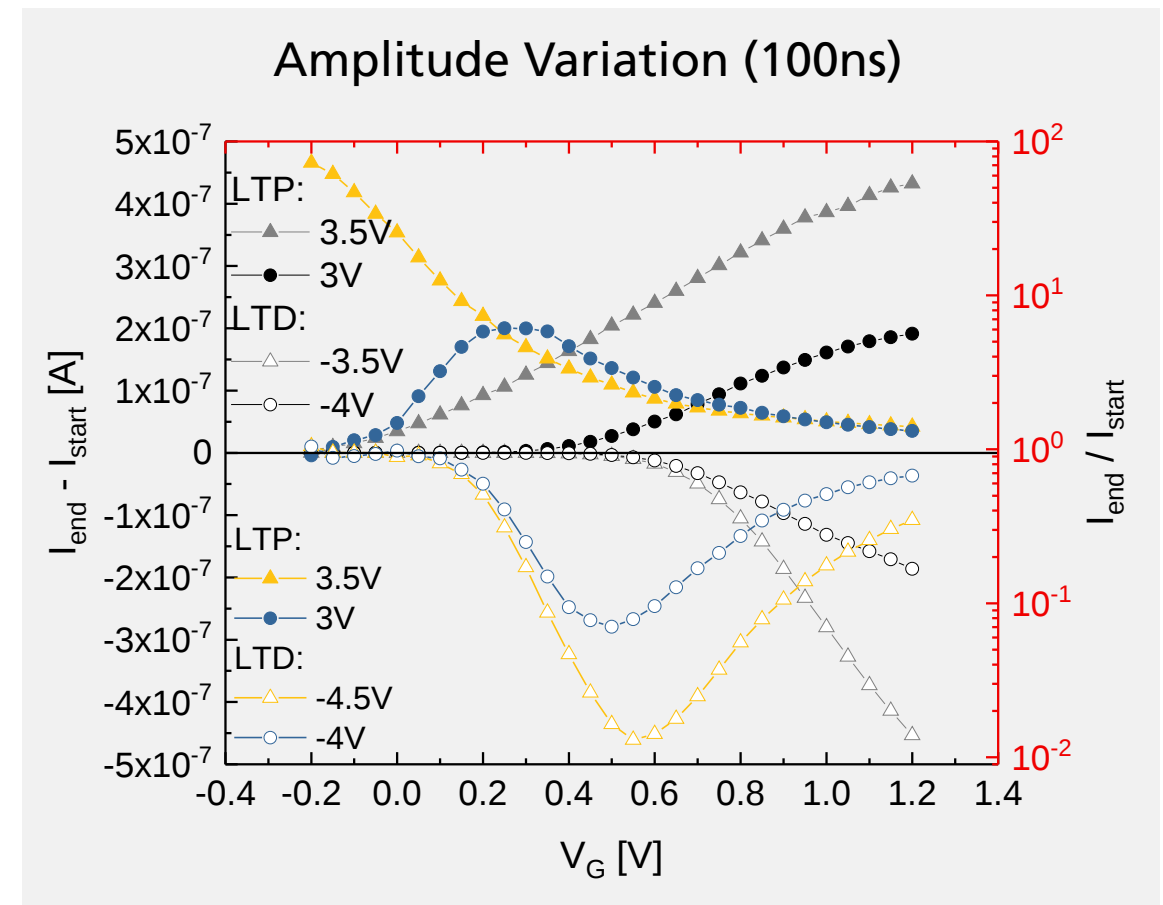
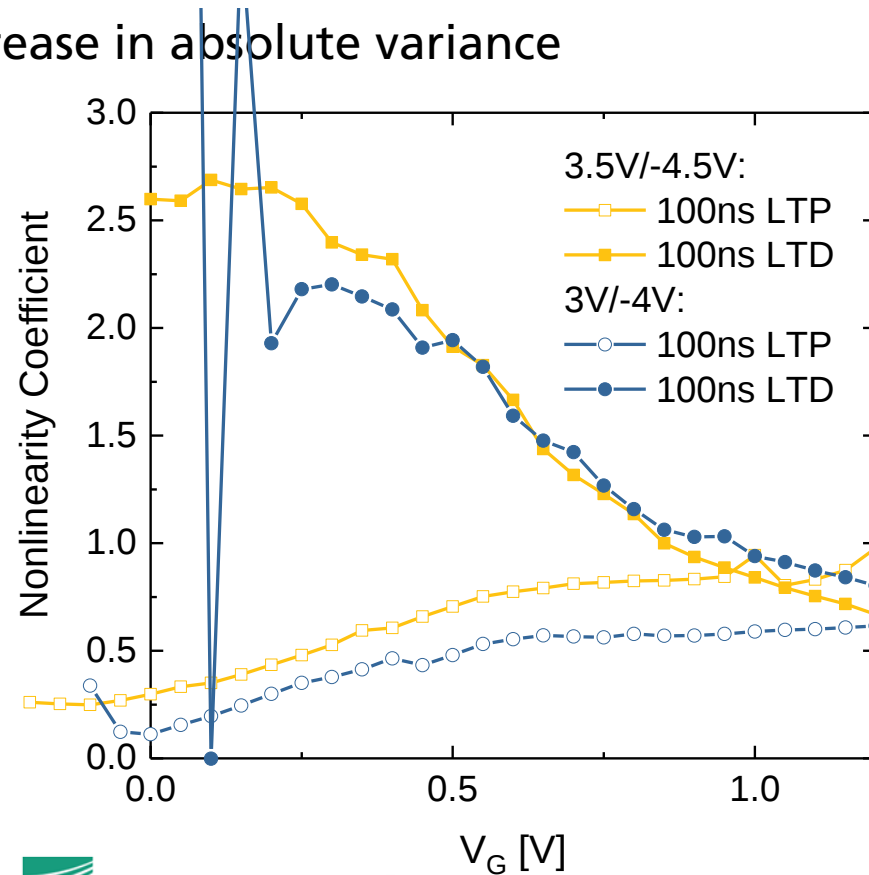


Sequence 1: Pulse Amplitude

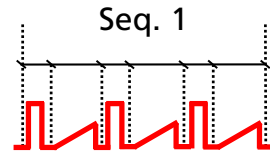


Amplitude reduction:

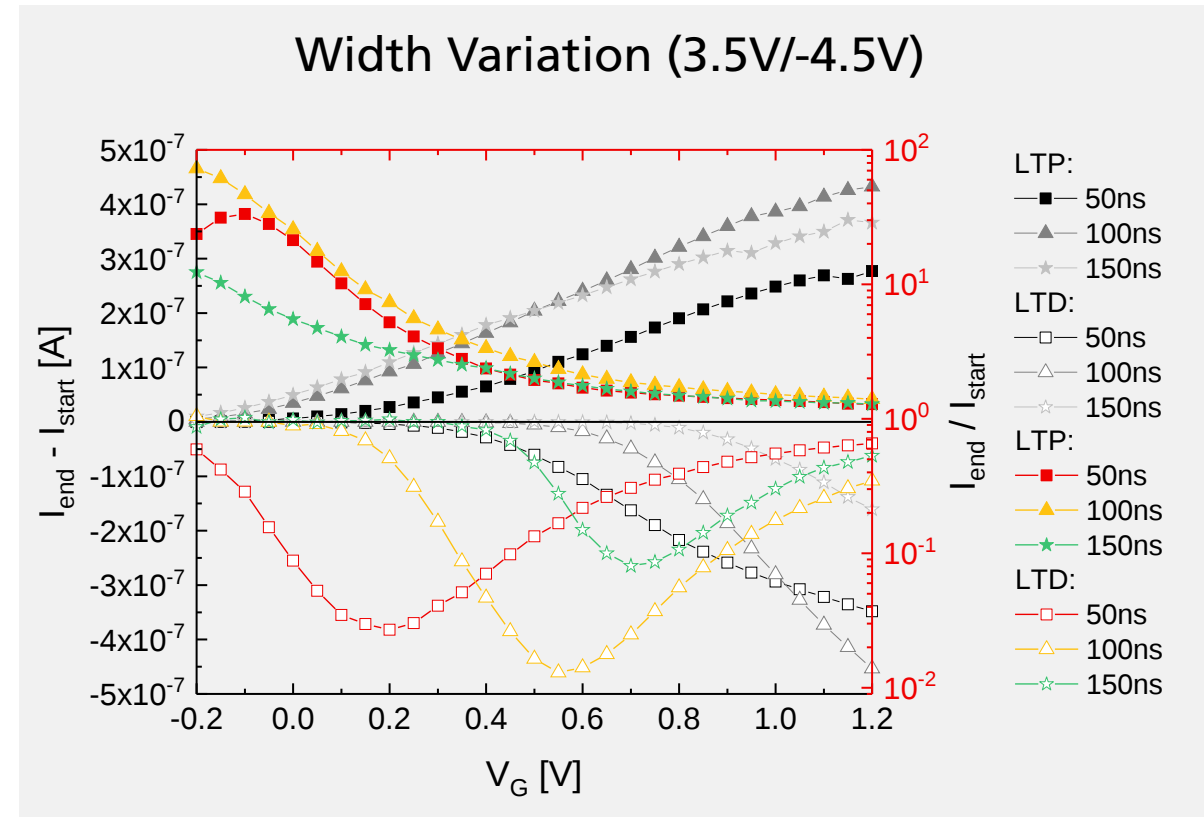
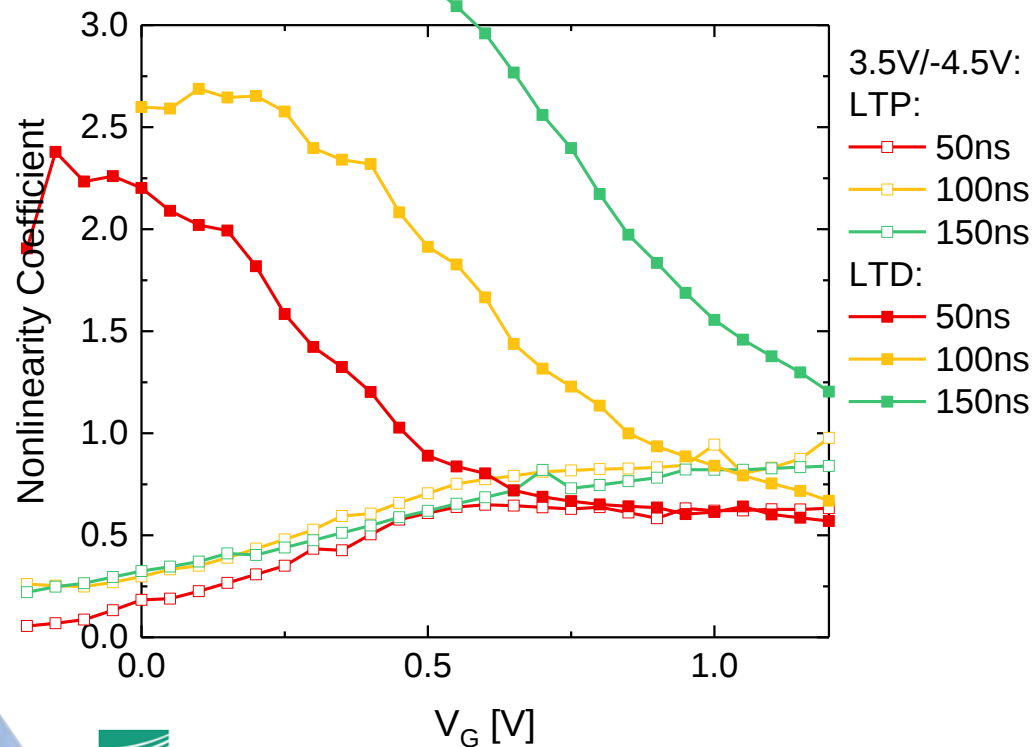
- Decrease of nonlinearity in potentiation
- Reduced assymetry of the variance
- Decrease in absolute variance



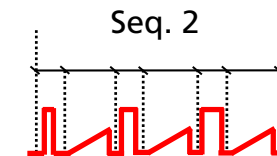
Sequence 1: Pulse Width



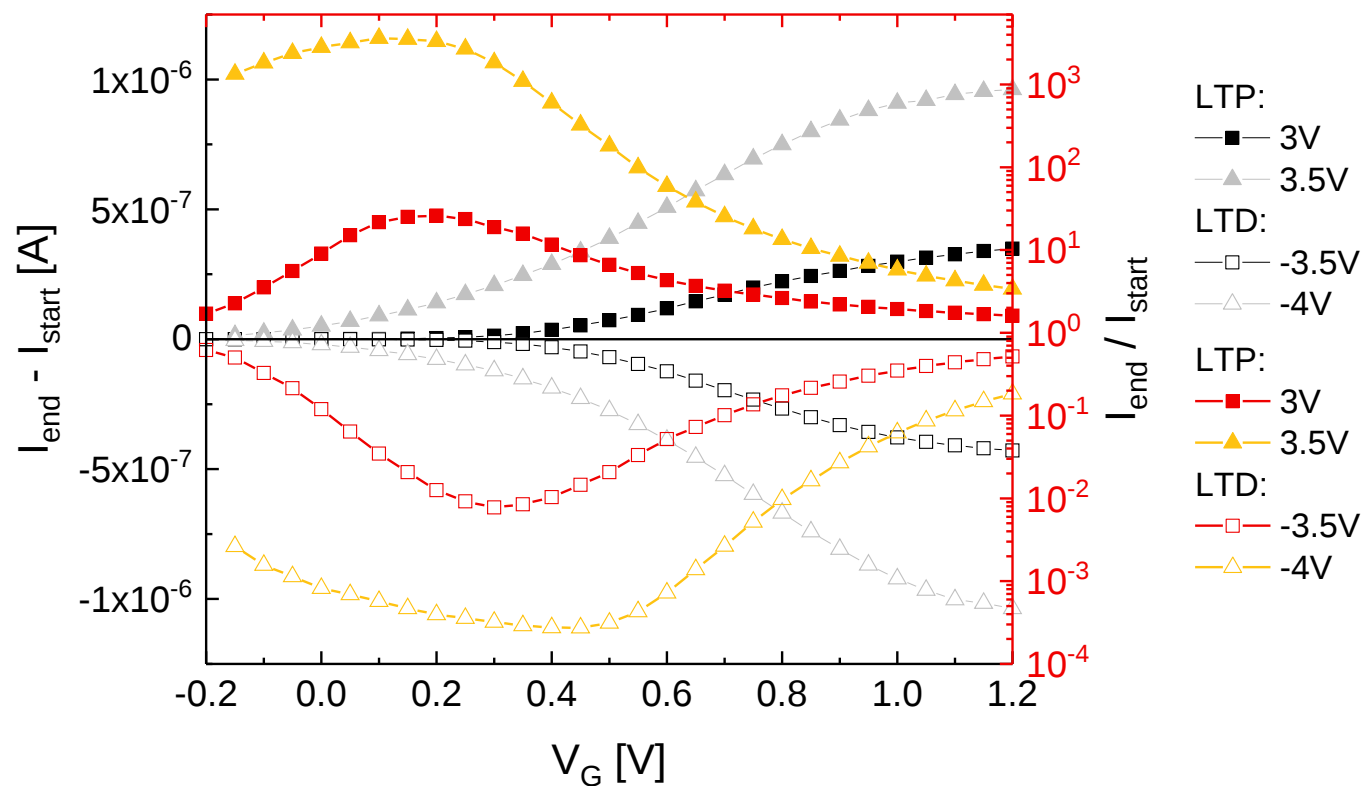
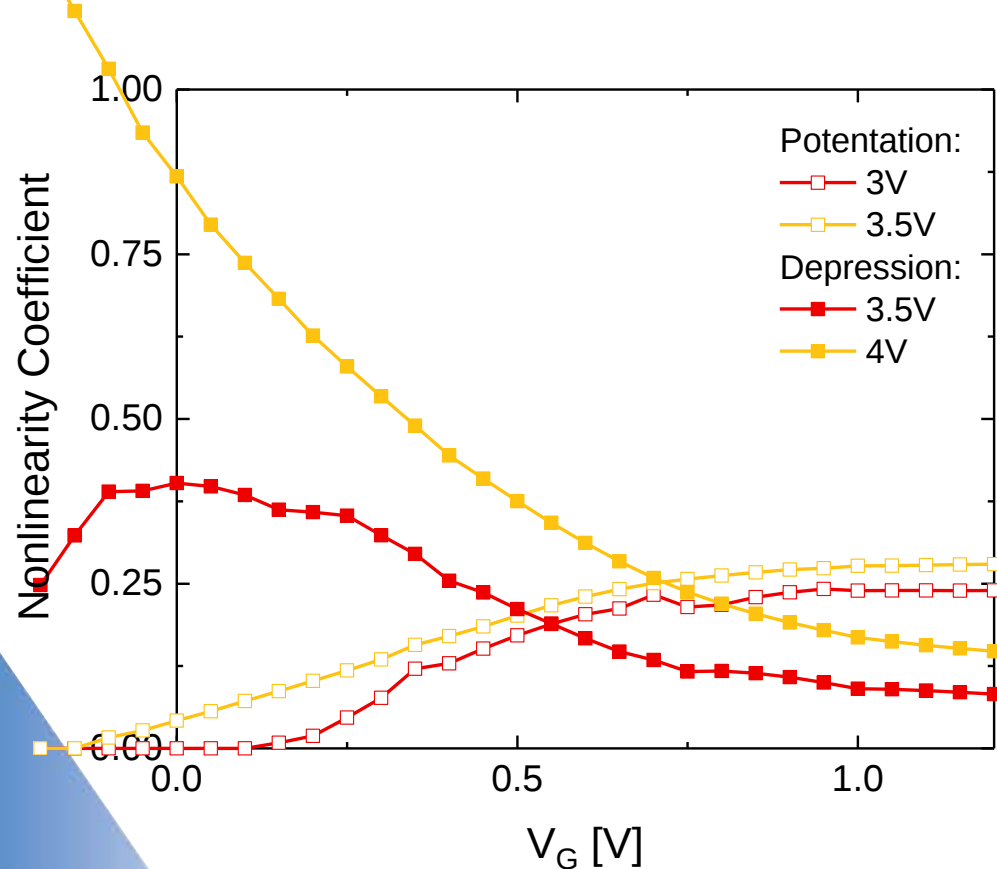
- Strong effect on depression
 - Moving to lower V_G
 - Converging at ~ 0.5
- No clear/strong influence on potentiation



Sequence 2: Pulse Amplitude



Trade-off between nonlinearity and variance



Sequence 3: Pulse Width

- Longer pulses increase slope of nonlinearity
- Absolute variance reaches maximum for 100ns
- Variance improvements with higher number of pulses

